

Title (en)
IMPLANT HAVING AN INCREASED NEGATIVE SURFACE CHARGE

Title (de)
IMPLANTAT MIT ERHÖHTER NEGATIVER OBERFLÄCHENLADUNG

Title (fr)
IMPLANT À CHARGE SUPERFICIELLE NÉGATIVE ÉLEVÉE

Publication
EP 3068452 A1 20160921 (DE)

Application
EP 14801977 A 20141112

Priority
• CH 19032013 A 20131114
• EP 2014074390 W 20141112

Abstract (en)
[origin: WO2015071322A1] The invention relates to an implant for implantation into a body. The implant comprises a surface that is provided for contact with the body or a body fluid when implanted and which surface has a first surface charge when in a first state. The surface assumes a second state having a second surface charge as a result of surface treatment, the second surface charge having a lower positive surface charge or a higher negative surface charge than the first surface charge. The implant is used for regulating an adsorption of proteins on the surface of the implant in terms of type, quantity and/or conformation of certain proteins by means of a defined second state of the surface, which has a defined second surface charge and/or a defined predetermined composition of an oxide layer of the surface.

IPC 8 full level
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Citation (search report)
See references of WO 2015071322A1

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